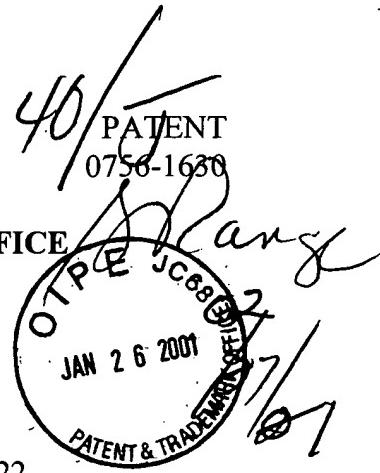


IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT application of:)
Shunpei YAMAZAKI et al.)
Serial No.: 08/799,506) Art Unit: 2822
Filed: February 12, 1997) Examiner: Wilczewski
For: METHOD FOR PROCESSING SEMICONDUCTOR)
DEVICE APPARATUS FOR PROCESSING A)
SEMICONDUCTOR AND APPARATUS FOR)
PROCESSING SEMICONDUCTOR DEVICE)



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January 26, 2000

Honorable Commissioner of Patents
Washington, D.C. 20231

Sir:

Responsive to the Office Action dated **September 26, 2000**, the period for response has been extended one (1) month until January 26, 2001, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

IN THE CLAIMS:

Please amend claims 80, 83, 86, 89, 92, 95, 98, 101, 104-109, 111, 112, 114-119, 121 and 122 as follows. Attached herewith is a marked-up copy of the amended claims.

80.(Amended) A multi-chamber system comprising:

a first chamber for irradiating a laser light to a semiconductor film formed over a substrate under an oxidizing atmosphere;

a second chamber for depositing a gate insulating film on said semiconductor film; and